



Assumptions



- Electrical and optical hybrids not burnt-in prior to arrival at UCSB/FNAL
 - No burn-in program for foreseen before full production
- Rod components currently scheduled to arrive much later than module components (~6 month)
 - Large supply of finished modules prior to rod construction
 - Minimal information of long-term stability of most components
 - Necessitates burn-in of a fraction of modules prior to rod construction

Sample each construction jig periodically
- Vienna cold box and rod burn-in only systems viable for such a program
 - Vienna cold box software already tested and written



UCSB Short-term Testing Plan



- **Characterize hybrid (+PA) on arrival**
 - Basic functionality and deep test (ARC)
 - Specific bad channel requirements for hybrid (+PA)
- **Re-characterize module on completion of construction**
 - Basic functionality, deep test, IV curves (ARC)
 - Different bad channel requirement for module
- **Vienna cold box test fraction of modules (DAQ)**
 - Acts as ~24 hour module burn-in
 - Scaled bad channel requirements for change in gain, grounding, etc.
 - Identifies mechanical/bond/electrical weaknesses prior to production of large number of modules
 - Reduces reworking of rod/retrofitting of modules



Deep Test Modifications



- Make bad channel requirements specific to component type tested
→ (hybrid, hybrid+PA, module)
- Remove/loosen relative percentage/sigma requirements
- Tighten/add fixed requirements
- Motivate requirements on silicon tracker performance



Pedestal/Noise Test



- Increase minimum noise test
 - Fractional requirements too wide to discern saturated/dead FE preamplifier
- Replace fractional pedestal requirements with $|P_i - P_{\text{chip}}| < P_{\text{cut}}$
 - P_{cut} motivated by decrease in dynamic range of channel
- Special requirements on chip edges if necessary



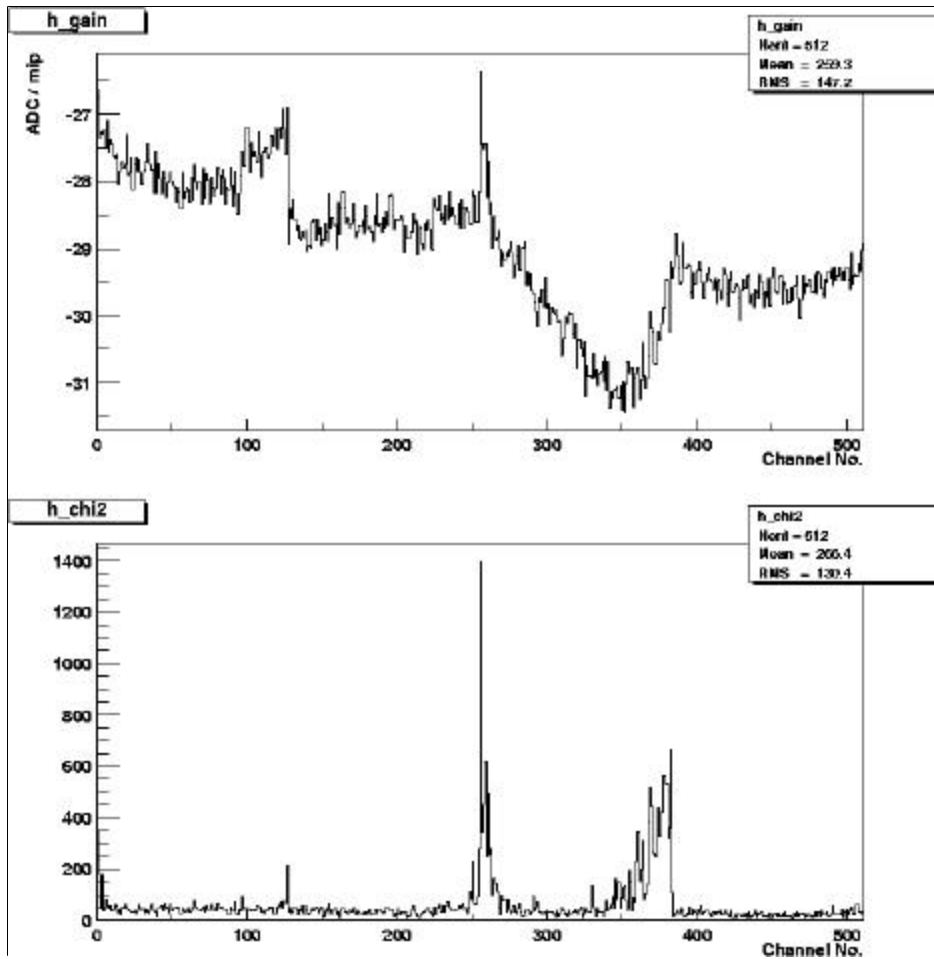
Pulse Shape Test



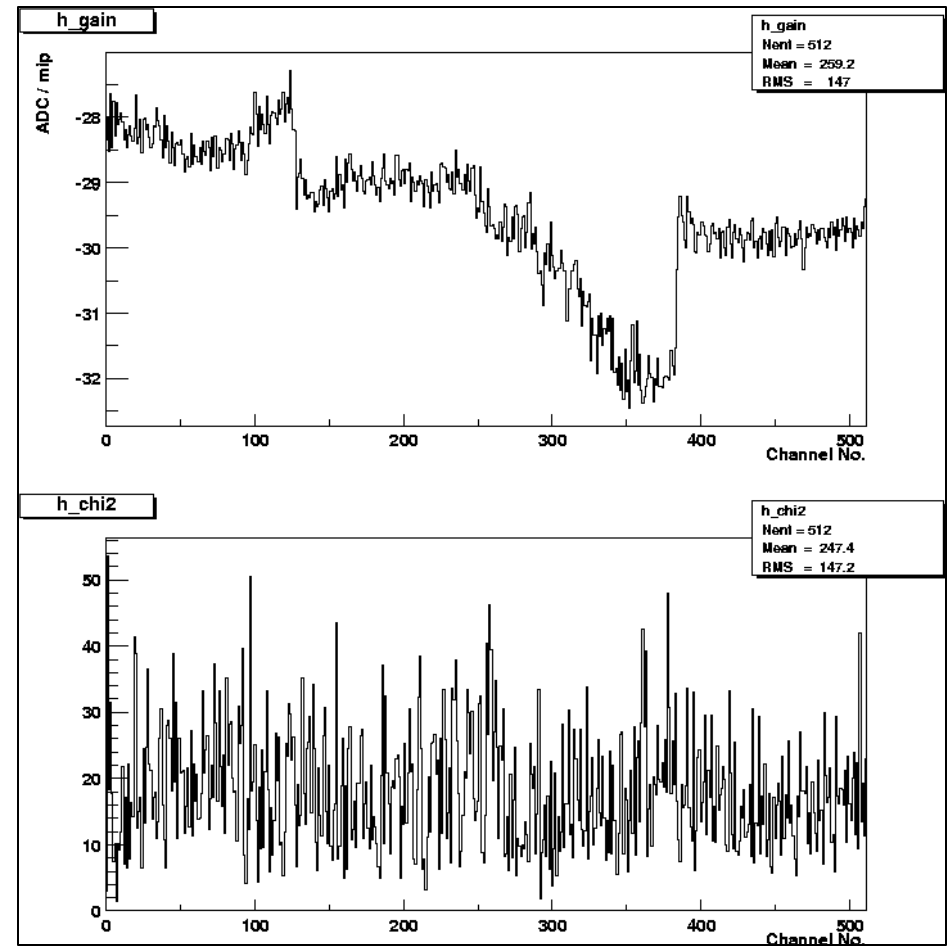
- Remove current pulse shape requirements
 - Include rise-time/fall-time/peak-time requirement
- Replace pulse shape with gain measurement
 - Measure pulse heights at 6-13 calibration injection setting between 0-3 MIPs and fit
 - Require gain between G_{low} and G_{high}
 - Gain uniformity specification
 - Calibration circuit may not be uniform
 - Require $\chi^2 < \chi^2_{\text{cut}}$ (χ^2 based on noise measurement)
 - Finds non-linear charge response and gain non-uniformities
- Should be relatively simple to include in ARC software
- See following example



Hybrid Gain Measurement(1)



0-3 MIPs



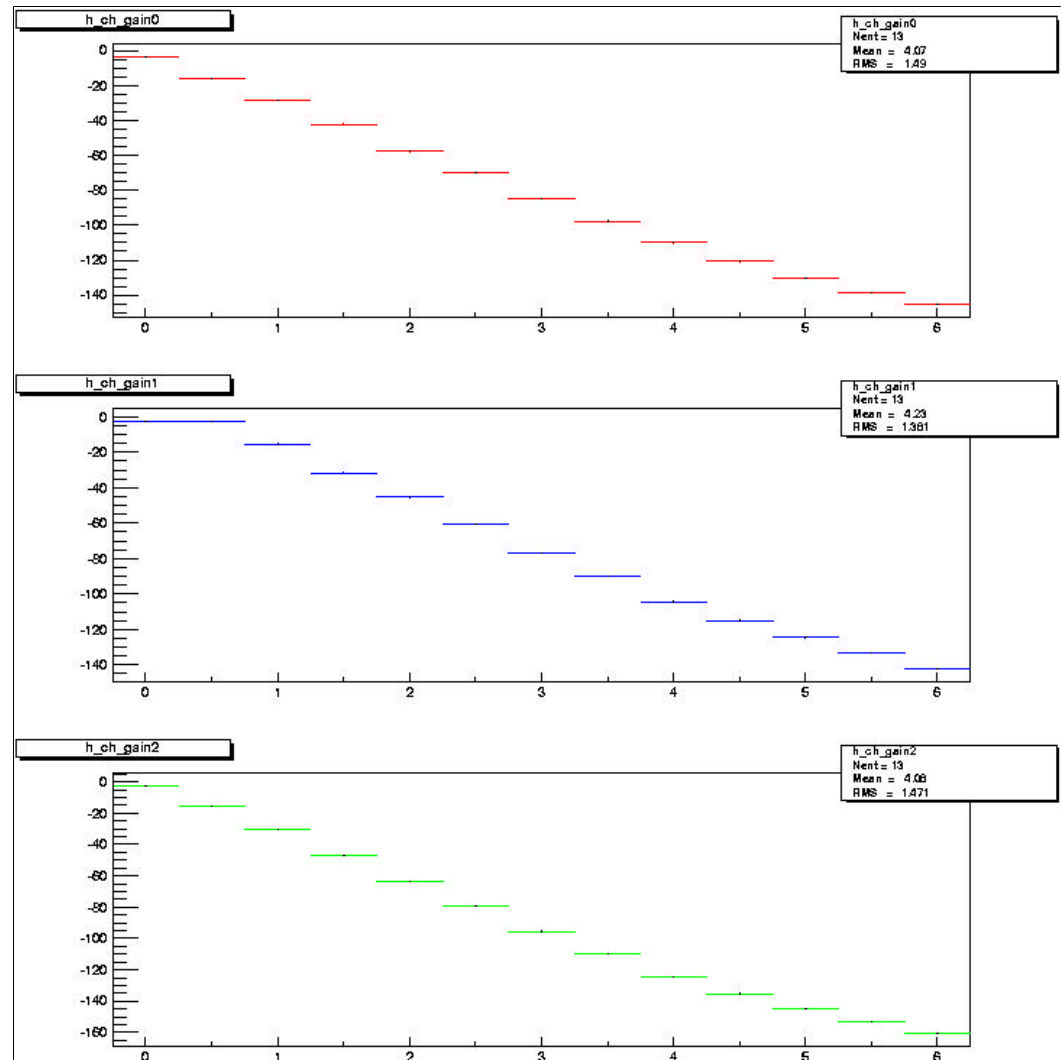
0.25-3 MIPs



Hybrid Gain Measurements(2)



- Three channels' pulse height vs. MIP injected
 - First 'regular'
 - Second 1st channel of chip 3
 - Third 63th channel of chip 3
- Gain non-uniform and bad χ^2 if 0 MIP point included for chip 3
- Improved if 0 MIP excluded
- Mostly likely calibration circuit non-uniformities





Pipeline Test



- Add pipeline capacitor pedestal/noise requirement
 - Widen relative to channel requirement according to decreased statistics
- Add pipeline column pedestal/noise requirement
- Remove bad capacitors/columns from channel pedestal/noise calculation



Ladder Grading



- Grade ladders by fraction of bad capacitors
 - Bad channel=190 capacitors
 - Bad column=128 capacitors
- Treat chip edges differently (if necessary)



Necessary Infrastructure



- DAQ with 10 hybrid channels
- LV/HV power supplies
 - Reusable for rod burn-in
- Vienna cold box
- DI/O PC board
- 1.5 kW chiller
- Module carriers